

DISCUSSION OF THE AMENDMENT

Claims 1, 21 and 22 have each been amended by inserting that said arylamines contain no styryl group and no styrylene group. While such language does not appear in the specification *in haec verba*, none of the numerous arylamines exemplified in the specification at pages 35-48 contain a styryl group or a styrylene group.

One skilled in the art would have understood that the above was inherent. *See, e.g., Kennecott Corp. v. Kyocera Int'l, Inc.*, 835 F.2d 1419, 5 USPQ2d 1194 (Fed. Cir. 1987) (term "equiaxed microstructure" not literally disclosed held to be inherent property of claimed sintered ceramic body); *In re Wright*, 866 F.2d 422, 9 USPQ2d 1649 (Fed. Cir. 1989) (term "not permanently fixed thereto" not literally disclosed held to be described by absence of disclosure of permanently fixed microcapsules); and *In re Voss*, 557 F.2d 812, 194 USPQ 267 (CCPA 1977) (term "crystalline content . . . at least 50% by weight" not literally disclosed held to be described by literal disclosure of "glass-ceramic material" coupled with evidence that one skilled in the art would have attributed the recited crystalline content as inherent in that material). **Copies of *Kyocera*, *Wright*, and *Voss* are enclosed.**

No new matter is believed to have been added by the above amendment. Claims 1 and 20-22 remain pending in the application.

REMARKS

The rejection of Claims 1 and 20-22 under 35 U.S.C. § 102(e) as anticipated by US 6,534,199 (Hosokawa et al), is respectfully traversed.

Hosokawa et al is drawn to an organic EL device which contains an organic light emitting medium comprising (A) at least one compound selected from the group consisting of monostyryl derivatives containing amine, distyryl derivatives containing amine, tristyryl derivatives containing amine and tetrastyryl derivatives containing amine and (B) at least one compound selected from a Markush group of anthracene derivatives (column 2, lines 34-60). Thus, the aryl amines of Hosokawa et al must containing a styryl or styrylene group (column 3, line 27ff). Such groups are excluded by the above-amended claims. Accordingly, it is respectfully requested that this rejection be withdrawn.

The rejection of Claims 1 and 20-22 on the ground of nonstatutory obviousness-type double patenting over Claims 1 and 4 of Hosokawa et al, is respectfully traversed.

The claims of Hosokawa et al also require that the amine therein contain the above-discussed styryl or styrylene groups, which are now excluded by the above-amended claims. Accordingly, it is respectfully requested that this rejection be withdrawn..

All of the presently-pending claims in this application are now believed to be in immediate condition for allowance. Accordingly, the Examiner is respectfully requested to pass this application to issue.

Respectfully submitted,

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